

**REMARKS**

This is responsive to the final Official Action mailed September 17, 2007. A Petition for a three-month Extension of Time, with Fee, is filed concurrently. Accordingly, this response is timely.

An RCE (with fee) is filed concurrently. Thus Claim 1 is to be amended in accordance with this Response, and Claims 1, 4, 15, 17, 26, 29-42 and 45 – 49 are currently pending with claims 34-37 having been withdrawn from consideration.

It is noted with appreciation that no claims were rejected based upon 35 U.S.C. § 102.

The rejections of record based upon 35 U.S.C. §103 are respectfully traversed as will be explained below.

Claim 1 is an independent claim, with Claims 4, 15, 17, 26, and 28 – 33 depending from Claim 1 either directly or indirectly.

Claim 38 is an independent claim with Claims 13, 39-49 depending from Claim 38 either directly or indirectly.

1. **Rejection based on Rossi in view of Turner**

The prior rejection of Claims 1, 4, 13, 15, 17, 26, 29, 32, and 38-42 based on the combination of the **Rossi** and **Turner** documents (Paragraph 7, pages 2-4 of the Office Action) is believed to be moot as to Claims 1, 4, 15, 17, 26, 29, and 32. The reason Applicant takes this position is because Claim 2 was not included in the rejection, and the language from Claim 2 has now been added to Claim 1. The prior rejection as to Claims 13 and 38-42 is respectfully traversed for the following reasons.

The **Rossi** document is directed to "methods for forming ordered nanometer-scale arrays of metal or semiconductor junctions on a semiconductor surface by means of 'natural lithography'".(Rossi, col. 1, lines 21-24). According to the Rossi document, "Natural lithography refers to a technique in which a crystalline colloid mono- or bilayer is assembled on the surface of a substrate to form a mask. A second material is deposited through the spaces between the colloid particles onto the surface of the substrate." (Rossi, col. 1, lines 51-55). In the lithography process disclosed by the **Rossi** document, the crystalline colloid monolayer or bilayer is "formed on the substrate surface by withdrawing the substrate surface from the sol of colloid particles" (Rossi, col. 3, lines 40-42) which "can be from

plastics or inorganic materials..." (Rossi, col. 4, lines 18-20). Such a masking method allows nanopatterning of a coating on a substrate (See, Rossi, col. 3, line 51 and col. 4, lines 46-50). The nanoscale features on the substrate is provided by the spaces between the particles of spherical form and strongly depends on their size and arrangement.

The **Rossi** document discloses only natural lithography method for forming the mask, not the "screen" of independent Claim 1.

The **Turner** document teaches (Turner, col. 8, line 50 to col. 9, line 5) that an inorganic maskant is applied by screen printing for patterning a substrate prior to the coating of metallic conductive films.

It would not be obvious to one of ordinary skill in the art as of Applicants' priority date to modify the process of the **Rossi** document by incorporating the screen printing method of the **Turner** document to apply the mask. First, the method of the **Rossi** document already discloses a method for forming a mask and this method (natural lithography) is well-described and numerous advantages are given, the main one being the providing of nanoscale features on the substrate. The disclosure of the **Rossi** document would thus not induce one of ordinary skill in the art, who desired to apply a mask prior to coating a substrate, to seek another, different or supplementary method, than the one already present in the **Rossi** document. No problems with the method of the **Rossi** document are suggested which would lead anyone of ordinary skill to seek a different or alternative method.

If, arguendo, one of ordinary skill in the art, having the knowledge and benefit of the **Rossi** document, would search for another method, the person of ordinary skill would have immediately rejected and never have used the screen printing process of the **Turner** document because, at least based on the disclosures of those two documents, the methods are not compatible. They are not compatible because nothing in the **Turner** document remotely suggests that the method therein described would allow for nanopatterning (which is the objective of the disclosure in the **Rossi** document) but only permits the micro-scale inherently due to the diameter of the threads constituting the screen.

As a consequence, amended Claims 13 and 38-42 are not obvious based on the combination of the disclosures of the **Rossi** document and the **Turner** document, and it is respectfully submitted that the rejection should be withdrawn.

2. **Rejection based on Rossi in view of Turner and Boaz**

The prior rejection of Claims 2 (now canceled) 3 (now canceled) 15, 28-33 and 45-49 based on the combination of the **Rossi**, **Turner** and **Boaz**, as set forth in paragraph 8, pages 4-5 of the Office Action, is respectfully traversed for the following reasons.

The disclosures of the **Rossi** and **Turner** documents has been described above.

The **Boaz** document discloses a method for applying a masking material to a surface of a glass sheet in order to further apply an opaque screened area through the mask (Boaz, col. 1, lines 10-13). The mask of the **Boaz** document has macroscopic features because it defines the edges of the opaque screened area to be applied to the glass sheet (Boaz, col. 2, lines 62-64) and because the masking material covers all the central area of the glass sheet (Boaz, col. 4, lines 40-41). Moreover, the disclosure of the **Boaz** document relates to windshields or backlites in vehicles (Boaz, col. 1, lines 14).

First, for the reasons given with respect to the rejection based on the combination of the **Rossi** and **Turner** documents, it is submitted that even adding the disclosure of the **Boaz** document would not render the claims obvious.

Second, there is no reason in the record to suggest that one of ordinary skill in the art of semiconductor devices, at the appropriate time, would have considered the disclosure of the **Boaz** document which relates to a different, non-analogous technology, namely, windshields and backlites in vehicles, and then added those features to, or modified the features of, the disclosures of the **Rossi** document and the **Turner** document. One reason is that the disclosure of the **Boaz** document relates to masking at the macroscopic scale, not the micro-scale of the **Turner** document or the nanoscale of the **Rossi** document.

Third, if, arguendo, one of ordinary skill in the art, having the knowledge and benefit of the **Rossi** document and the **Turner** document would search for some additional features or some basis to modify the features disclosed in the **Rossi** and/or **Turner** documents, again such person would immediately rejected and never have used the features described in the **Boaz** document because, at least based on the disclosures of those three documents, the

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methods are not compatible. They are not compatible because nothing in the **Boaz** document remotely suggests that the method therein described would allow for nanopatterning (which is the objective of the disclosure in the **Rossi** document) or even masking at the micro-scale which is the inherent subject addressed by the disclosure of the **Turner** document (due to the diameter of the threads constituting the screen) when due consideration is given to the fact that the disclosure of the **Boaz** document relates to masking at macro scale, e.g., windshields and backlites in vehicles.

As a consequence, Claims 15, 28-33 and 45-49, are not obvious based on the combination of the disclosures of the **Rossi** document and the **Turner** document and the **Boaz** document, and it is respectfully submitted that the rejection should be withdrawn.

#### CONCLUSION

Based on the foregoing reconsideration and withdrawal of all rejections is solicited.

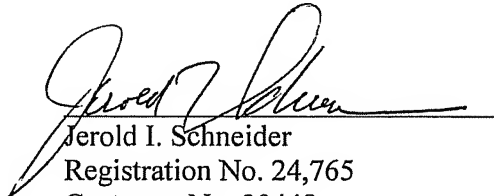
Applicants respectfully submit that the application is now in condition for allowance. Favorable consideration is respectfully requested.

If any points remain in issue which the Examiner feels may be best resolved through an interview, the Examiner is respectfully requested to contact the undersigned at the telephone number listed below.

Respectfully submitted,

AKERMAN SENTERFITT

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